

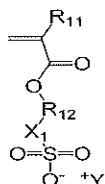
ABSTRACT

HYDROPHILIC PHOTOACID GENERATOR AND RESIST COMPOSITION

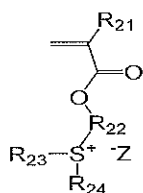
COMPRISING SAME

Disclosed are a hydrophilic photoacid generator prepared by copolymerization of a first (meth)acrylic acid ester having a structure represented by the following Formula 1 or 2, with a polymerizable monomer selected from the group consisting of a second (meth)acrylic acid ester, an olefin-based compound and a mixture thereof, each of which contains a functional group selected from the group consisting of a hydroxyl group, a carboxyl group, a lactone group, a nitrile group and a halogen group:

[Formula 1]



[Formula 2]



wherein respective substituents are defined in the specification, and a resist composition comprising the same.

The hydrophilic photoacid generator is uniformly dispersed in a resist film, thus improving a line edge roughness of resist patterns.